

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of: Confirmation Number: 7419
FUKIAGE et al.

Application No.: 10/702,049 Group Art Unit: 1792

Filed: November 6, 2003 Examiner: Tadayyon Eslami, Tabassom

Title: METHOD OF IMPROVING POST-DEVELOP PHOTORESIST PROFILE ON
A DEPOSITED DIELECTRIC FILM

RESPONSE TO NON-FINAL REJECTION

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

In response to the Non-Final Office Action dated December 24, 2008, the due date for response to which being March 24, 2009, please amend the above-identified application as follows: